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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
10/710,199	06/25/2004	Chih-Wei Yang	13875-US-PA	4198	
31561 75	590 05/16/2006		EXAM	EXAMINER	
JIANQ CHYUN INTELLECTUAL PROPERTY OFFICE			LE, DUNG ANH		
7 FLOOR-1, N ROOSEVELT	O. 100 ROAD, SECTION 2		ART UNIT	PAPER NUMBER	
TAIPEI, 100			2818		
TAIWAN			DATE MAILED: 05/16/2006	6	

Please find below and/or attached an Office communication concerning this application or proceeding.

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	Application No.	Applicant(s)				
Office Action Commence	10/710,199	YANG ET AL.				
Office Action Summary	Examiner	Art Unit				
	DUNG A. LE	2818				
The MAILING DATE of this communication ap Period for Reply	opears on the cover sheet w	ith the correspondence addres	SS			
A SHORTENED STATUTORY PERIOD FOR REPI WHICHEVER IS LONGER, FROM THE MAILING [ - Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication If NO period for reply is specified above, the maximum statutory period - Failure to reply within the set or extended period for reply will, by statu Any reply received by the Office later than three months after the maili earned patent term adjustment. See 37 CFR 1.704(b).	DATE OF THIS COMMUNI .136(a). In no event, however, may a d will apply and will expire SIX (6) MOI te, cause the application to become A	CATION. reply be timely filed  NTHS from the mailing date of this commu BANDONED (35 U.S.C. § 133).				
Status						
1)⊠ Responsive to communication(s) filed on <u>21 l</u>	<u>March 2006</u> .					
2a)⊠ This action is <b>FINAL</b> . 2b)□ Th	•					
3) Since this application is in condition for allows	ance except for formal mat	ters, prosecution as to the me	erits is			
closed in accordance with the practice under	Ex parte Quayle, 1935 C.D	D. 11, 453 O.G. 213.				
Disposition of Claims						
4)⊠ Claim(s) <u>14-20</u> is/are pending in the application	on.					
4a) Of the above claim(s) is/are withdra	awn from consideration.					
5) Claim(s) is/are allowed.						
6)⊠ Claim(s) <u>14-20</u> is/are rejected.						
7) Claim(s) is/are objected to.						
8) Claim(s) are subject to restriction and/	or election requirement.					
Application Papers						
9) The specification is objected to by the Examin	er.					
10)⊠ The drawing(s) filed on <u>25 June 2005</u> is/are:	a)⊠ accepted or b)⊡ obje	ected to by the Examiner.				
Applicant may not request that any objection to the	e drawing(s) be held in abeya	nce. See 37 CFR 1.85(a).				
Replacement drawing sheet(s) including the corre	ction is required if the drawing	(s) is objected to. See 37 CFR 1	.121(d).			
11)☐ The oath or declaration is objected to by the E	Examiner. Note the attache	d Office Action or form PTO-1	52.			
Priority under 35 U.S.C. § 119						
12) Acknowledgment is made of a claim for foreig a) All b) Some * c) None of:	n priority under 35 U.S.C.	§ 119(a)-(d) or (f).				
1. Certified copies of the priority documer	nts have been received.					
2. Certified copies of the priority documer		Application No.				
3. Copies of the certified copies of the price			ge ·			
application from the International Burea			-			
* See the attached detailed Office action for a lis	t of the certified copies not	received.				
Attachment(s)	🗖 .		le			
Notice of References Cited (PTO-892)     Notice of Draftsperson's Patent Drawing Review (PTO-948)		Summary (PTO-413) s)/Mail Date	_			
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/08 Paper No(s)/Mail Date		nformal Patent Application (PTO-152	2)			

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#### Claim Rejections

## Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 14- 17 and 19-20 are rejected under 35 U.S.C. 103 (a) as being unpatentable over Eppich et al. (2004/0178458 A1) in view of Chau et al. (6,696,345 B2).

Eppich et al. teach a MOS transistor, comprising:

- a substrate 16,
- a gate dielectric layer 22 on the substrate,
- a stacked gate on the gate dielectric layer, comprising,

from bottom to top, a first barrier layer 24, an interlayer 30, a work-function-dominating layer is conductively doped material 32 [0039], and second barrier layer 34 and a cap layer; and

a source/drain 52 in the substrate beside the gate (Figs. 2- 6 and related text).

Eppich et al. do not teach the work-function-dominating layer comprises a metallic material and a poly-si layer on the second barrier.

Chau et al. teach the work-function-dominating layer comprises a metallic material and 216 and a poly-si layer 220 on the second barrier 218 (col 2,lines 45-50 and Figs. 2 and 3J and related texts).

It would have been obvious to a person of ordinary skill in the art at the time the invention was made to form the work-function-dominating layer comprises a metallic material and a poly-si layer on the second barrier in Eppich et al. 's structure/device in order to avoid the danger of metal diffusion into a work-function-dominating layer and the gate dielectric layer.

Regarding claim 15, wherein the interlayer 30 (Eppich in [0038]) includes a material capable of controlling a crystal orientation of the work-function-dominating layer to adjust a work function of the work-function-dominating layer.

Regarding claim 16, wherein the interlayer includes a material capable of wetting a surface of the first barrier layer (Eppich in [0038]).

Regarding claim 17, wherein a thickness of the interlayer 30 is smaller than a thickness of the work-function-dominating layer 32 (figs 2-6).

Regarding claim 19, wherein the gate dielectric layer comprises a high-K dielectric layer 22 (Eppich in [0035]).

#### Regarding claim 20, further comprising:

a spacer 48 on a sidewall of the gate; and

a pair of lightly doped drains in the substrate,

wherein the source/drain is in the substrate beside the spacer, and the lightly doped drains are in the substrate beside the gate connecting with the source/drain (Figs. 2-3J).

### Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claim 18 is rejected under 35 U.S.C. 103 (a) as being unpatentable over.

Eppich et al. in view of Chau et al. and further in view of the remark.

Eppich et al. in view of Chau et al. teach the claimed invention as applied to claim 14 except for a thickness of the work-function-dominating layer is larger than a total thickness of the first and second barrier layers as cited in current claim.

However, it would have been obvious to one of ordinary skill in the art at the time the invention was made to form the work-function-dominating layer having a thickness is larger than a total thickness of the first and second barrier layers, since it has been held that where the general conditions of a claim are disclosed in the prior art, discovering the optimum or working ranges involves only routine skill in the art.

When responding to the office action, Applicants' are advice to provide the examiner with the line numbers and page numbers in the application and/or references cited to assist the examiner to locate the appropriate paragraphs.

A shortened statutory period for response to this action is set to expire 3 (three) months and 0 (zero) day from the day of this letter. Failure to respond within the period for response will cause the application to become abandoned (see M.P.E.P 710.02(b)).

#### Conclusion

Applicant's amendment necessitated the new ground(s) of rejection presented in this Office action. Accordingly, **THIS ACTION IS MADE FINAL**. See MPEP § 706.07(a). Applicant is reminded of the extension of time policy as set forth in 37 CFR 1.136(a).

A shortened statutory period for reply to this final action is set to expire THREE MONTHS from the mailing date of this action. In the event a first reply is filed within TWO MONTHS of the mailing date of this final action and the advisory action is not

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mailed until after the end of the THREE-MONTH shortened statutory period, then the shortened statutory period will expire on the date the advisory action is mailed, and any extension fee pursuant to 37 CFR 1.136(a) will be calculated from the mailing date of the advisory action. In no event, however, will the statutory period for reply expire later than SIX MONTHS from the date of this final action.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Dung A. Le whose telephone number is (571) 272-1784. The examiner can normally be reached on Monday-Tuesday and Thursday 6:00am- 4:00 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms can be reached on (571) 272-1787. The central fax phone numbers for the organization where this application or proceeding is assigned are (571)272-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

PRIMARY EXAMINER